



[TuC2] Advanced Metrology & Inspection, Process Diagnostics & Control, and Yield Management II

Session Date	November 11 (Tue.), 2025
Session Time	14:50-16:20
Session Room	Room C (Grand Ballroom 3, 2F)
Session Chair	Dr. WooSeok Kang (KIMM, Korea)

[TuC2-1] [Invited] 14:50-15:20

The Future Is Here: Next-Gen Semiconductor Metrology & Inspection

Taeyong Jo, Jinwoo Ahn, Jaewon Lee, Jeonghoi Kim, Hansaem Park, Myungjun Lee, and Sangjin Hyun (Samsung Electronics Co., Ltd., Korea)

[TuC2-2] [Invited] 15:20-15:50

The Importance and Role of MI in Semiconductor Devices' 3D Era

Byoung-Ho Lee (Hitachi High-Tech Corp., Japan)

[TuC2-3] [Invited] 15:50-16:20

Overlay Metrology for Layer Alignment Accuracy in Device Processing

Nahee Park (KLA Corp., USA)